ABSTRACT

Appropriate evaluation is enabled of in-plane distribution of resist sensitivity of a resist layer.

A resist sensitivity evaluation method for evaluating the resist sensitivity of a resist layer includes: a process of forming a resist coating film on a surface of a base-member (S12); a process of measuring the film thickness of the resist coating film and generating a first film thickness map (S13); a process of heat treating the resist coating film to give a resist layer (S14); a process of measuring the film thickness of the resist layer and generating a second film thickness map (S15); a process of using the first film thickness map and the second film thickness map to generate a pre-post heat treatment resist film reduction ratio map (S16); and a process of evaluating the resist sensitivity distribution of the resist layer based on the resist film reduction ratio map (S17).